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U.S. Department of Commerce, Patent and Trademark Office					Docket No.: AM-2390.D2			
Serial No.: 09/918,136					RECEIVED			
Applicant: Jianming FU								
Filing Date: July 30, 2001 SEP 11 2001					Group: unknown			
<div style="border: 1px solid black; border-radius: 50%; padding: 10px; display: inline-block;">             AUG 29 2001              PATENT &amp; TRADEMARK OFFICE           </div>					TC 1700			
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
HC	AA	4,239,611	12/16/80	Morrison, Jr.	204	298		
HC	AB	4,312,731	1/26/82	Morrison, Jr.	204	192 R		
HC	AC	4,444,643	4/24/84	Garrett	204	298		
HC	AD	4,601,806	7/22/86	Wirz	204	298		
HC	AE	4,652,358	3/24/87	Deppisch et al.	204	298		
HC	AF	4,746,417	5/24/88	Ferenbach et al.	204	298		
HC	AG	4,810,346	03/07/89	Wolf et al.	204	298		
HC	AH	4,818,561	4/4/89	Strahl	427	38		
HC	AI	4,872,964	10/10/89	Suzuki et al.	204	298		
HC	AJ	4,943,361	7/24/90	Kakehi et al.	204	192.32		
FOREIGN PATENT DOCUMENTS (Translation)								
		Document Number	Date	Country	Class	Subclass	Yes	No
HC 1	AK	62-89864	04/24/87	JP	—	—	X	
HC 2	AL	63-282263	11/18/88	JP	—	—	X	
HC 3	AM	64-28921	1/31/89	JP	—	—		X
HC 4	AN	1-268868	10/26/89	JP	—	—		X
HC 5	AO	5-1373	1/8/93	JP	—	—		X
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
HC	AP	Matsuoka et al., "Dense plasma production and film deposition by new high-rate sputtering using an electric mirror," <i>Journal of Vacuum Science and Technology A</i> , vol. 7, no. 4, Jul/Aug 1989, pp. 2652-2657						
HC	AQ	B. Window et al. "Charged particle fluxes from planar magnetron sputtering sources", <i>J. Vac. Sci. Technol. A</i> , vol. 4, no. 2, Mar/Apr 1986, pp. 196-202						
HC	AR	J. Musil, et al. "Unbalanced magnetrons and new sputtering systems with enhanced plasma ionization", <i>J. Vac. Sci. Technol. A</i> , vol. 9, no. 3, May/June 1991, pp. 1171-1177						
HC	AS	W. Munz, "The unbalanced magnetron: current status of development", <i>Surface and Coatings Technology</i> , vol. 48, 1991, pp. 81-94						
Examiner <i>Y. Cane</i>			Date Considered <i>2/26/92</i>					

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
JC	AA	4,963,239	10/16/90	Shimamura et al.	204	192.12	
JC	AB	5,026,471	6/25/91	Latz et al.	204	298.19	
JC	AC	5,047,130	9/10/91	Akao et al.	204	192.12	
JC	AD	5,120,417	6/9/92	Takahashi et al.	204	192.12	
JC	AE	5,242,566	9/7/93	Parker	204	298.2	
JC	AF	5,248,402	9/28/93	Ballentine et al.	204	298.2	
JC	AG	5,252,194	10/12/93	Demaray et al.	204	298.2	
JC	AH	5,262,028	11/16/93	Manley	204	192.12	
JC	AI	5,284,564	02/08/94	Maass	204	298.2	
JC	AJ	5,320,728	6/14/94	Tepman	204	192.12	

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		Document Number	Date	Country	Class	Subclass	Yes	No
JC 6	AK	62-230971	10/9/87	JP	1	1	X	
JC 7	AL	7-252651	10/03/95	JP	1	1	X	
JC 8	AM	7-166346	06/27/95	JP	1	1		X
JC 9	AN	9-41135	02/10/97	JP	1	1	X	
JC 10	AO	10-088339 A	04/07/98	JP	1	1	abstract	
JC 11	AP	11-74225	3/16/99	JP	1	1	X	
JC 12	AR	0-620-583A 1	10/19/94	EP	1	1	X	
JC 13	AS	0 691 419 A 1	01/10/96	EP	1	1	X	
JC 14	AT	2 241 710 A	9/11/91	UK	1	1	X	

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

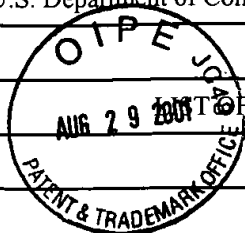
JC	AU	Posadowski et al., "Sustained self-sputtering using a direct current magnetron source," <i>Journal of Vacuum Science and Technology A</i> , vol. 11, no. 6, Nov/Dec 1993, pp. 2980-2984
1	AV	

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2/20/02

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U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
MC	AA	5,322,605	6/21/94	Yamanishi	204	298.07	
MC	AB	5,334,302	8/2/94	Kubo et al.	204	298.18	
MC	AC	5,415,754	05/16/95	Manley	204	192.12	
MC	AD	5,514,259	05/07/96	Shiota et al.	204	298.19	
MC	AE	5,536,362	7/16/96	Love et al.	156	643.1	
MC	AF	5,556,519	9/17/96	Teer	204	192.12	
MC	AG	5,584,971	12/17/96	Komino	204	192.13	
MC	AH	5,593,551	01/14/97	Lai	204	192.12	
MC	AI	5,746,897	5/5/98	Heimanson et al.	204	298.2	

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		Document Number	Date	Country	Class	Subclass	Yes	No
MC15	AL	5-325705	12/10/93	JP	—	—		X
MC16	AM	7-126844	5/16/95	JP	—	—	Abstract	
	AN							
	AO							
	AP							

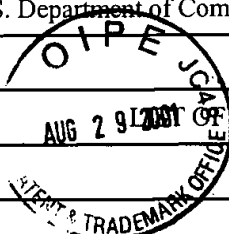
  

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
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MC	AA	5,770,025	6/23/98	Kiyota	204	298.2	
MC	AB	5,795,451	8/18/98	Tan et al.	204	298.2	
MC	AC	5,824,197	10/20/98	Tanaka	204	192.12	
MC	AD	5,879,523	3/9/99	Wang et al.	204	298.11	
MC	AE	5,897,752	4/27/99	Hong et al.	204	192.12	
MC	AF	5,966,607	10/12/99	Chee et al.	438	305	12/31/97
MC	AG	5,976,327	11/2/99	Tanaka	204	192.15	12/12/97
	AH						
	AI						

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